IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Inventors:

John F. Conley, Jr., Yoshi Ono, and

Wei Gao

Serial No: Not Yet Assigned

Filed: Herewith

Title: REACTIVE GATE ELECTRODE

CONDUCTIVE BARRIER

PATENT APPLICATION

Attorney Docket No. SLA0674

Hon. Commissioner for Patents Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Sir:

Listed on attached Form PTO-1449 is information submitted pursuant to 37 C.F.R. §1.56. A copy of each listed publication is submitted herewith.

Applicant respectfully requests that the listed information be considered by

the Examiner and made of record in the above-identified application.

February 23, 2004

(Date)

Respectfully submitted

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FORM PTO-1449 INFORMATION DISCLOSURE CITATION IN AN APPLICATION			DOCKET NUMBER SLA674 APPLICANT				
			Conley et al.				
			FILING DATE:	ING DATE: GROUP ART UNIT		UNIT	
		U.S. PATE	NT DOCUMENTS				
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FIL. DATE IF APPROP.	
		FOREIGN PA	TENT DOCUMENTS				
	DOCUMENT NUMBER	DATE	COUNTRY/NAME	CLASS	SUB CLASS	TRANSLATION YES NO	
		OTHER	DOCUMENTS				
	 V. Misra, G.P. Heuss, H. Zhong, "Use of metal-oxide-semiconductor capacitors to detect interactions of Hf and Zr gate electrodes with SiO₂ and ZrO₂," Appl. Phys. Lett. <u>78</u>, 4166 (2001). V. Misra, M. Kulkarni, G. Heuss, H. Zhong, and H. Lazar, "Electrical and Material Properties of Metal 						
	V. Misra, M. Kulkar Silicate Dielectrics of Proceedings Vol. 20	and Metal Gate Ele	ctrodes for Advanced CMOS	al ana maieria Devices," in E	lectrocher	nical Society	
							
EXAMINER			DATE CONSIDERED				